

Fig. 2

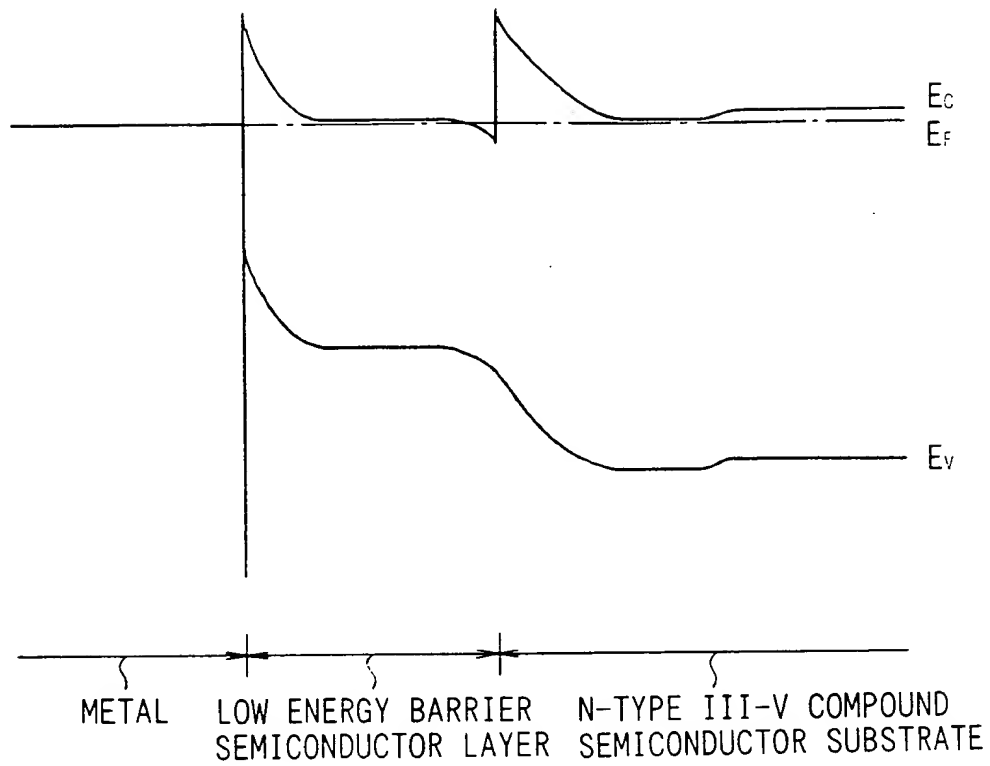


Fig. 3

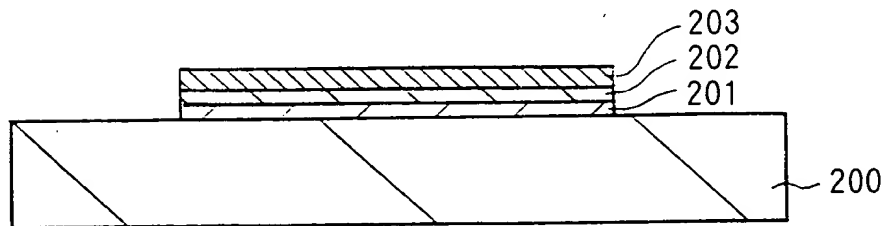


Fig. 4A

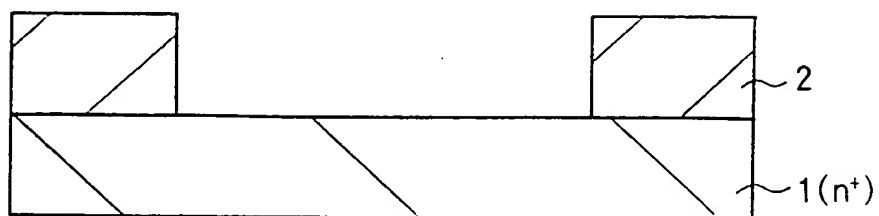


Fig. 4B

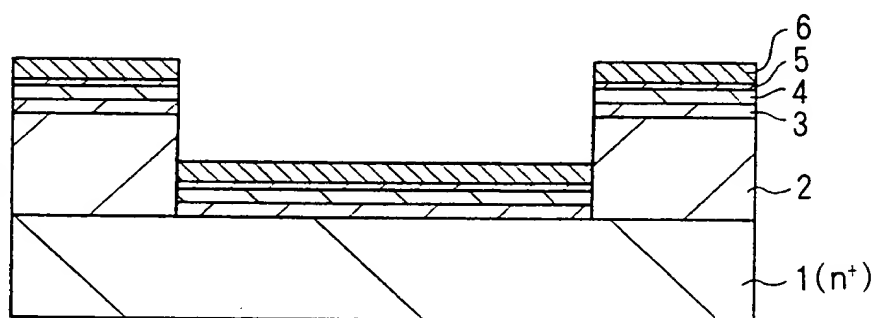


Fig. 4C

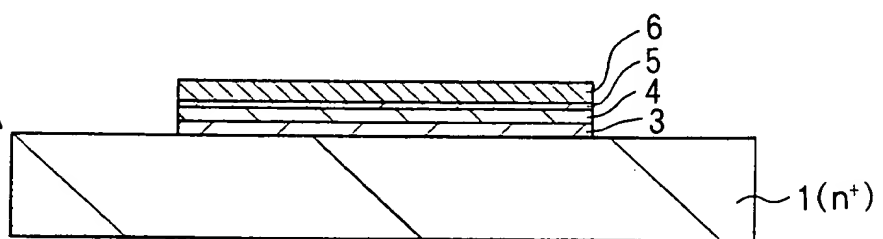


Fig. 4D

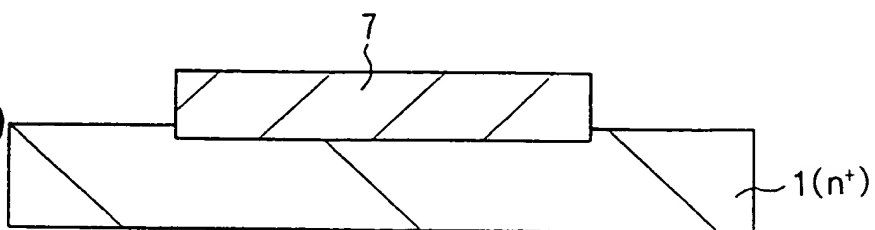


Fig. 5

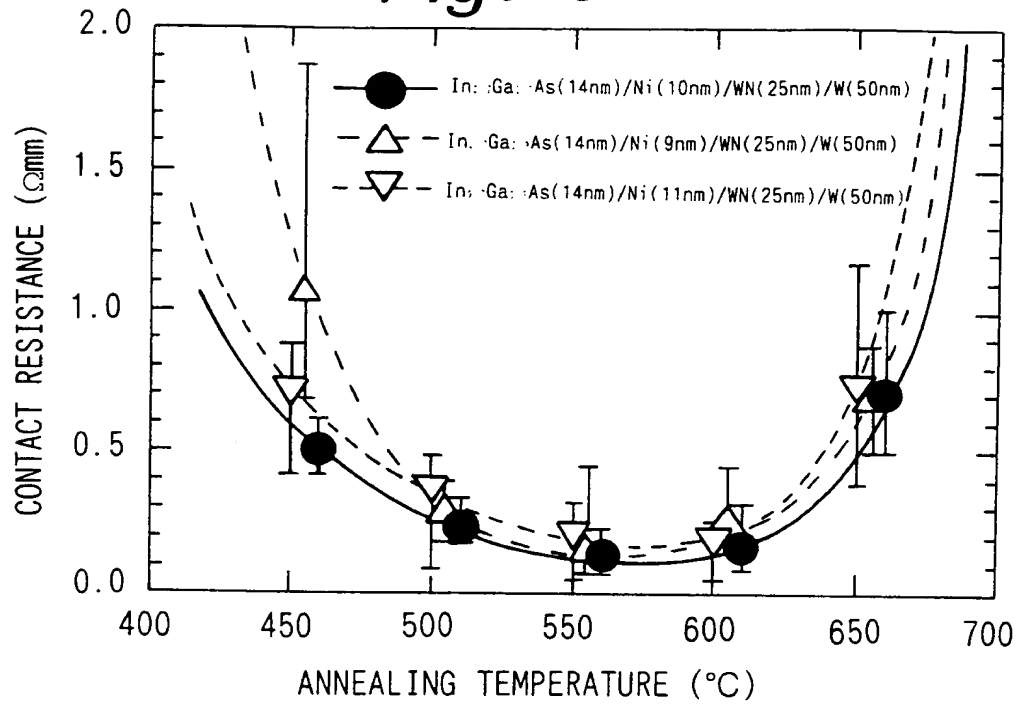


Fig. 7

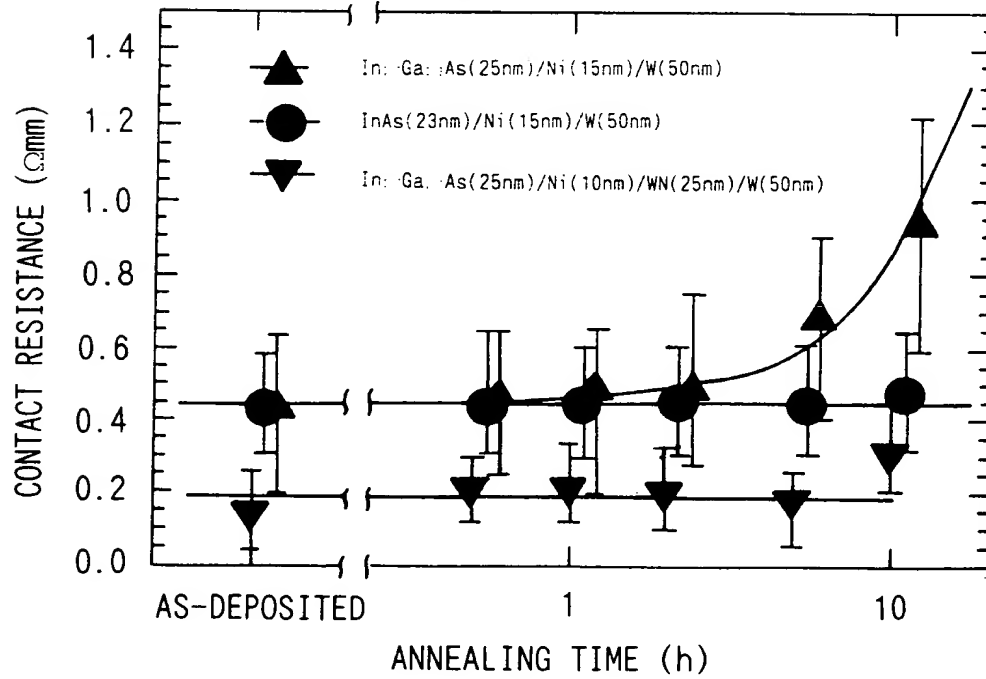
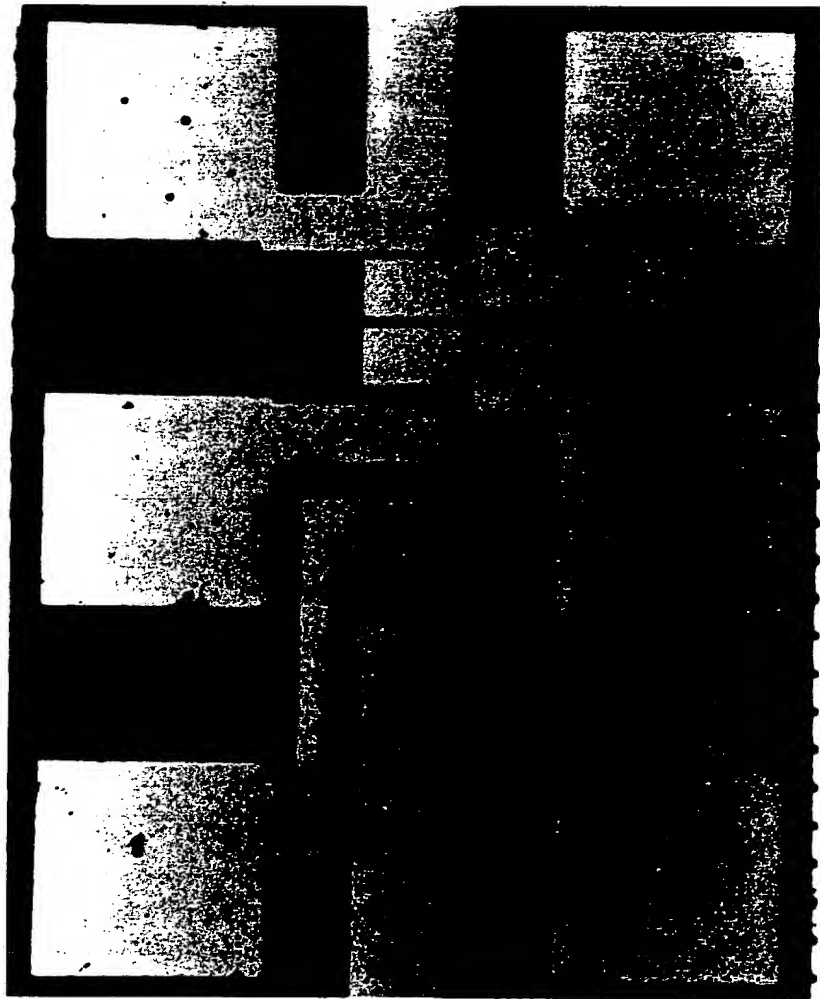


Fig. 6



50 μ m
└────────┘

Fig. 8

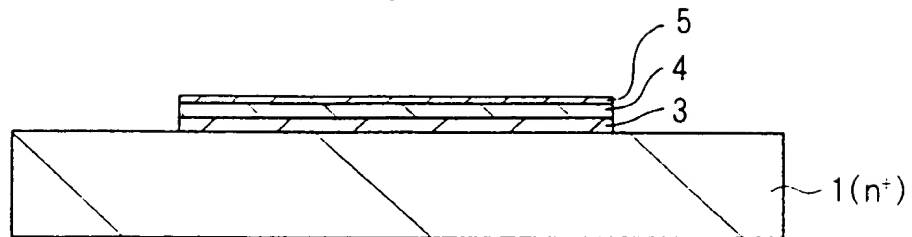
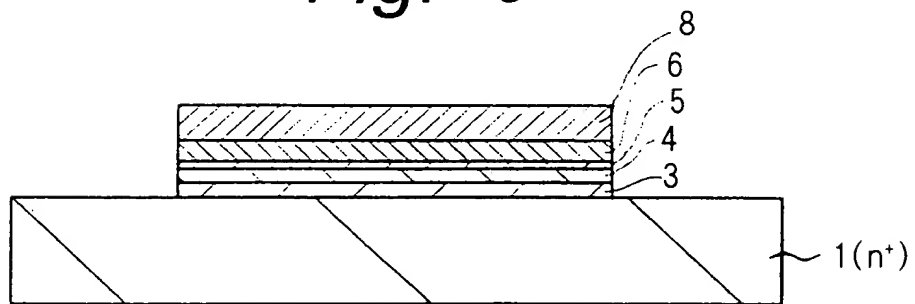
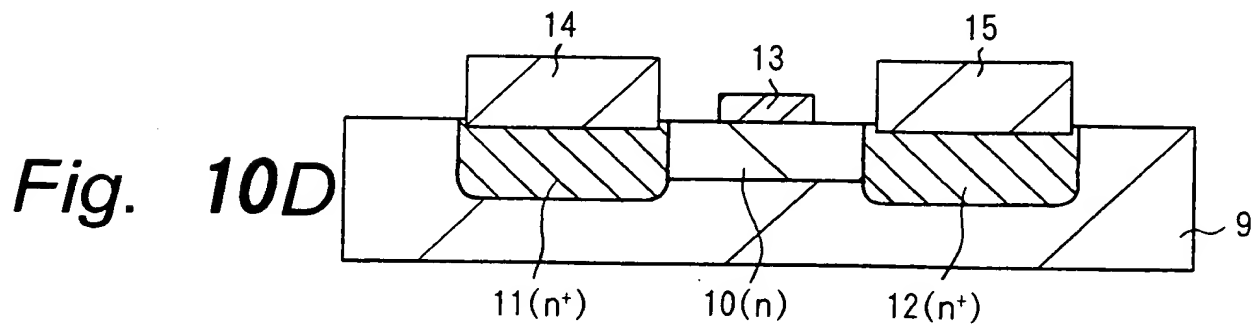
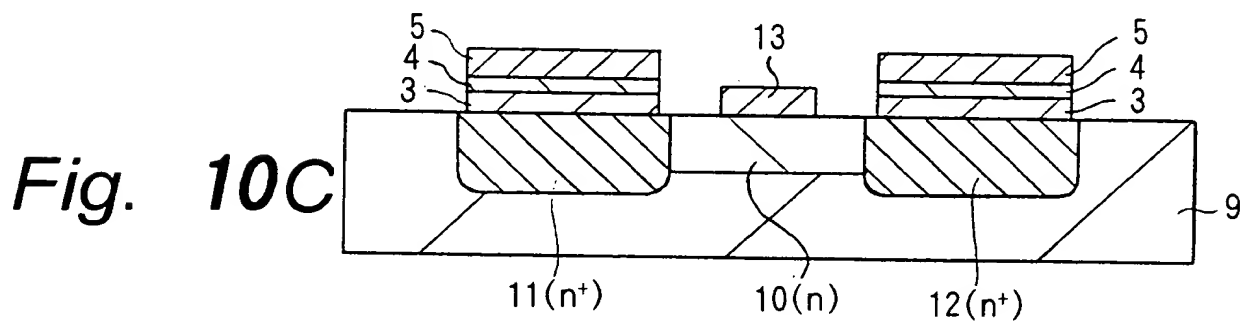
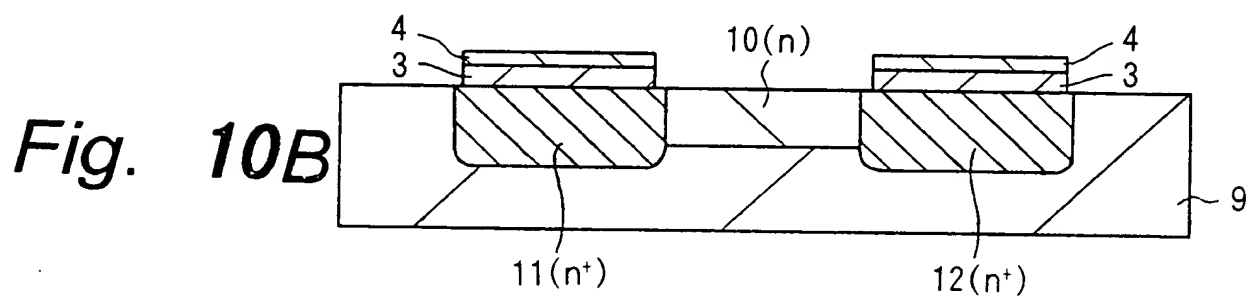
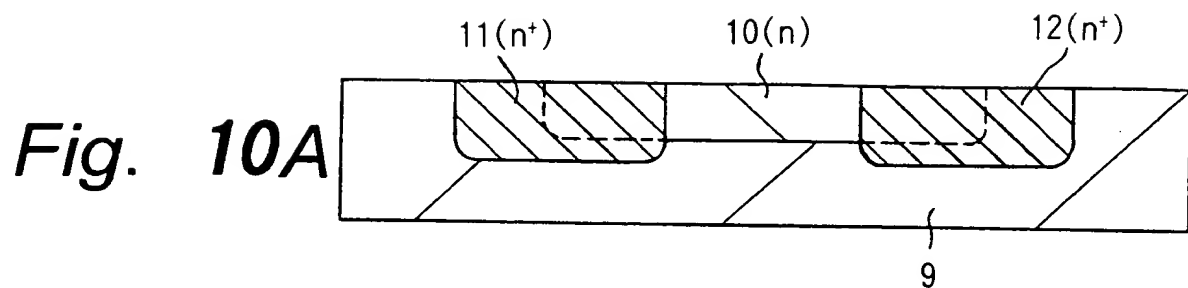


Fig. 9







- 1: n⁺-TYPE GaAs SUBSTRATE
- 3: NON-SINGLE CRYSTAL In_{0.7}Ga_{0.3}As LAYER
- 4: Ni FILM
- 5: WN FILM
- 6: W FILM
- 7: OHMIC ELECTRODE
- 8: Al FILM